

Abstract

Provided is a photoresist developing solution comprising (A), (B), (C), and (D). (A) is a quaternary ammonium ion represented by formula (1), (B) is a halide ion, (C) is a hydroxide ion, and (D) is water. (In the formula, R1, R2, R3, and R4 are each independently a C1-16 alkyl group; at least one of R1, R2, R3, and R4 is a C2-16 alkyl group; and not all of R1, R2, R3, and R4 are the same alkyl group.)

[FIG. 1]